

Summary of MOSFET Large Signal Model

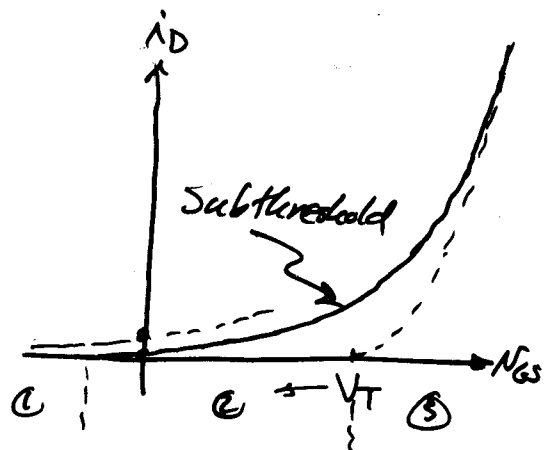
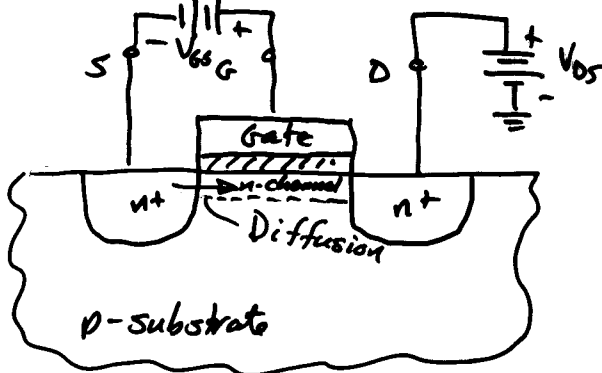
	Long channel	Short Channel ( $V_{sat}$ )
Linear $V_{DS} < V_{DS(sat)}$	$i_{DS} = k' \frac{W}{L} \left[ N_{GS} - V_T - \frac{V_{DS}}{2} \right] V_{DS}$	$i_{DS} = \frac{W}{L} \left( \frac{\mu C_{ox}}{1 + \frac{V_{DS}}{E_c L}} \right) \left( N_{GS} - V_T - \frac{V_{DS}}{2} \right) V_{DS}$
$V_{DS(sat)}$	$V_{DS(sat)} = N_{GS} - V_T$	$V_{DS(sat)} = \frac{(N_{GS} - V_T) E_c L}{(N_{GS} - V_T) + E_c L}$
Saturation $V_{DS} > V_{DS(sat)}$	$i_{DS} = \frac{k'}{2} \frac{W}{L} (N_{GS} - V_T)^2$	$i_{DS} = \frac{W \mu C_{ox} E_c}{2} \left[ \frac{(N_{GS} - V_T)^2}{(N_{GS} - V_T) + E_c L} \right]$

Download lecture 7 & 8 for next Wednesday

Subthreshold Conduction and Models

Weak inversion (subthreshold) operation occurs when

$N_{GS} < V_T$



- ① Substrate is not inverted if  $\phi_s < \phi_f$
- ② Channel is weakly inverted (diffusion current) -  $\phi_f < \phi_s < 2\phi_f$
- ③ Strong inversion (drift current) -  $2\phi_f < \phi_s$

Large Signal Model -

$$i_{\text{subthreshold}} = i_{\text{sub}} = I_s \exp\left(\frac{q(N_{GS} - V_T - V_{\text{offset}})}{m k T}\right) \left[1 - \exp\left(\frac{-q N_{DS}}{k T}\right)\right]$$

$$N_{GS} \leq V_T$$

$$i_{\text{sub}} = I_s \exp\left(\frac{q V_{\text{offset}}}{m k T}\right) \left[ \exp\left(\frac{q(N_{GS} - V_T)}{m k T}\right) \right] \left[1 - \exp\left(\frac{-q N_{DS}}{k T}\right)\right]$$

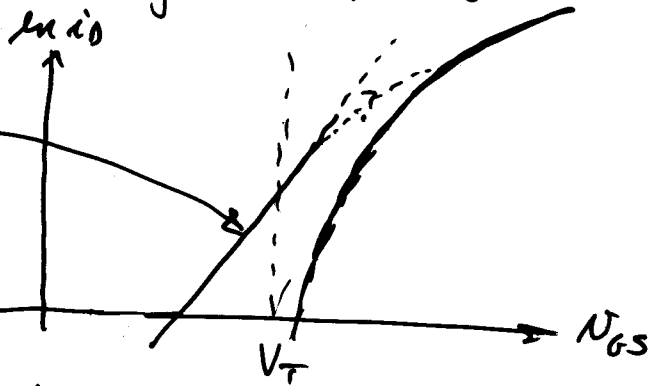
Finally,

$$i_{\text{sub}} = \frac{W}{L} I_x \exp\left[\frac{q(N_{GS} - V_T)}{m k T}\right] \left[1 - \exp\left(\frac{-q N_{DS}}{k T}\right)\right]$$

$$1.5 < m < 3$$

$$(1 + \lambda N_{DS}) \quad v_{DS} > 0$$

$$I_{DS} = I_{DS} (\text{strong inversion}) + I_{DS} (\text{weak inversion})$$



If  $i_{DS} \approx 1 \mu A$ , the MOSFET for modest  $\frac{W}{L}$ 's is in subthreshold.

Models -  $i_D = f(N_G, N_S, N_D, N_B)$

Ex. 2.11 (see next page)

Find the components of  $C_g$  in cutoff, linear & sat regions for a PMOS with  $t_{ox} = 22 \text{ \AA}$ ,  $W = 400 \text{ nm}$ ,  $L = 100 \text{ nm}$  and  $V_{GS} = 0$  in the cutoff region.

$$C_g = C_g W = \frac{\epsilon_{ox}}{t_{ox}} L W = \frac{(4)(8.85 \times 10^{-14})}{22 \times 10^{-8}} \times 400 \times 10^{-7} \times 100 \times 10^{-7}$$

$$= 0.64 \text{ fF}$$

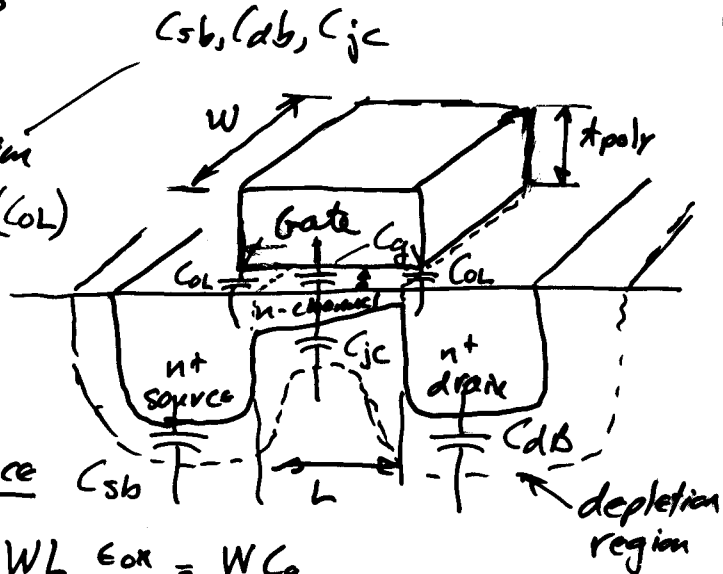
Cutoff:  $C_{GS} = C_{GD} = 0$ ,  $C_{GB} \approx \frac{1}{2} C_g = 0.32 \text{ fF}$ , Linear:  $C_{GS} = C_{GD} = 0.32 \text{ fF}$ ,  $C_{GB} = 0$

Saturation:  $C_{GS} = 0.43 \text{ fF}$ ,  $C_{GD} = 0$  &  $C_{GB} = 0$

Capacitances of a MOSFET

Types of capacitances

- 1.) Thin oxide ( $C_g$ )
- 2.) pn junction depletion
- 3.) Overlap (intrinsic) ( $C_{ol}$ )

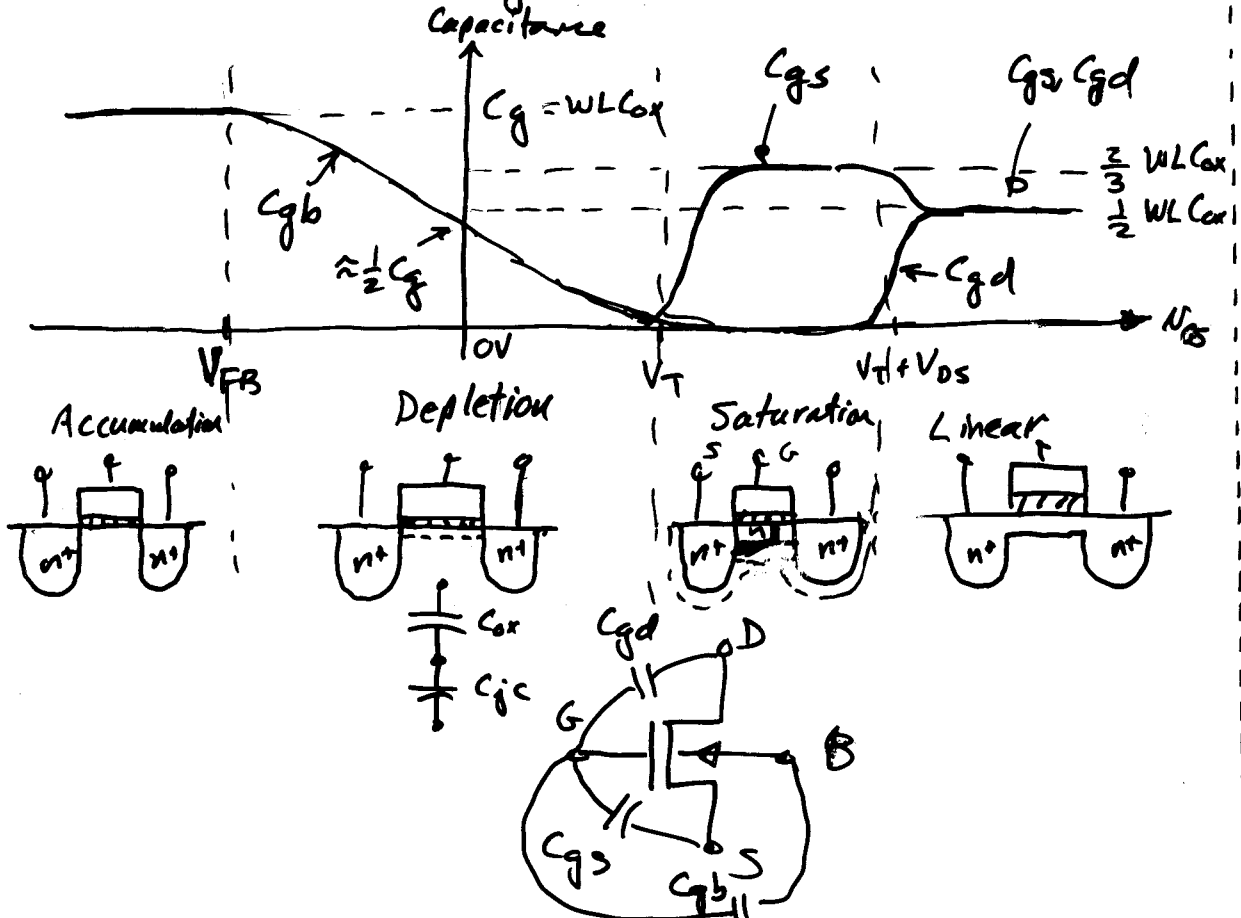


Thin-oxide capacitance

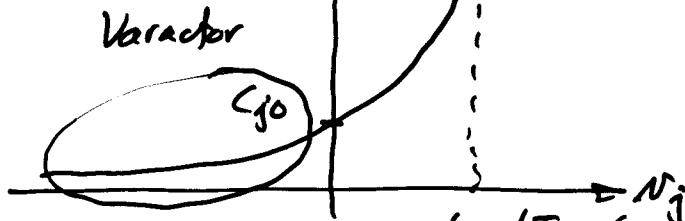
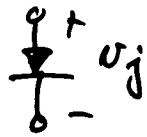
$$C_g = C_G = WL C_{ox} = WL \frac{\epsilon_{ox}}{x_{ox}} = W C_g$$

Decomposition of  $C_g$  into its parts-

$$V_{DS} \geq V_{DS} - V_T$$

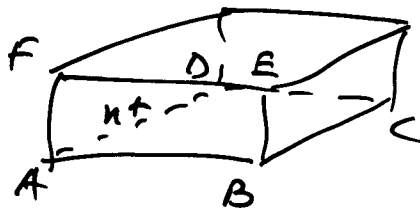


PN- Junction Capacitance



$$C_j = \frac{C_{j0}}{\left(1 - \frac{V_j}{\Phi_B}\right)^m} \quad \frac{1}{3} < m < \frac{1}{2}$$

$$\Phi_B = \frac{kT}{q} \ln \left( \frac{N_A N_D}{n_i^2} \right)$$



Bottom + Sidewall

Overlap Caps next